



Influence of <u>temperature</u>, <u>strain</u>, <u>alloy composition</u>, <u>doping</u>, and <u>film thickness</u> on the dielectric function of semiconductors

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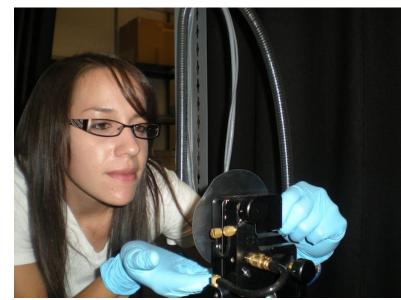
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AVS 65th International Symposium & Exhibition

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Awards

Submit Abstract

The Spectroscopic Ellipsometry Focus Topic integrates themes ranging from classical material science and thin film characterization to nanometer scale science and novel optical sensing concepts. We will host two oral sessions dedicated to traditional applications of spectroscopic ellipsometry in optical materials and thin film characterization as well as new and emerging topics. The first session will focus on classical research topics of ellipsometry as for instance optical coatings and inorganic thin films characterization.

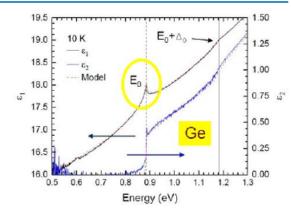


Figure courtesy Carola Emminger, Dept. of Physics, New Mexico State Univ., Las Cruces, NM

Furthermore, presentations on the ellipsometric investigation of novel optical and electronic materials and materials with subwavelength structures will be included. In the second oral session, we will host presentations on novel experimental and theoretical approaches including for instance imaging ellipsometry or optical critical dimension analysis techniques. As a highlight of our Spectroscopic Ellipsometry focus topic, the best student paper, which is selected based on the quality of the research, its presentation, and the discussion during the symposium, will be awarded with the Spectroscopic Ellipsometry Focus Topic student award. Spectroscopic Ellipsometry will also host a poster session.

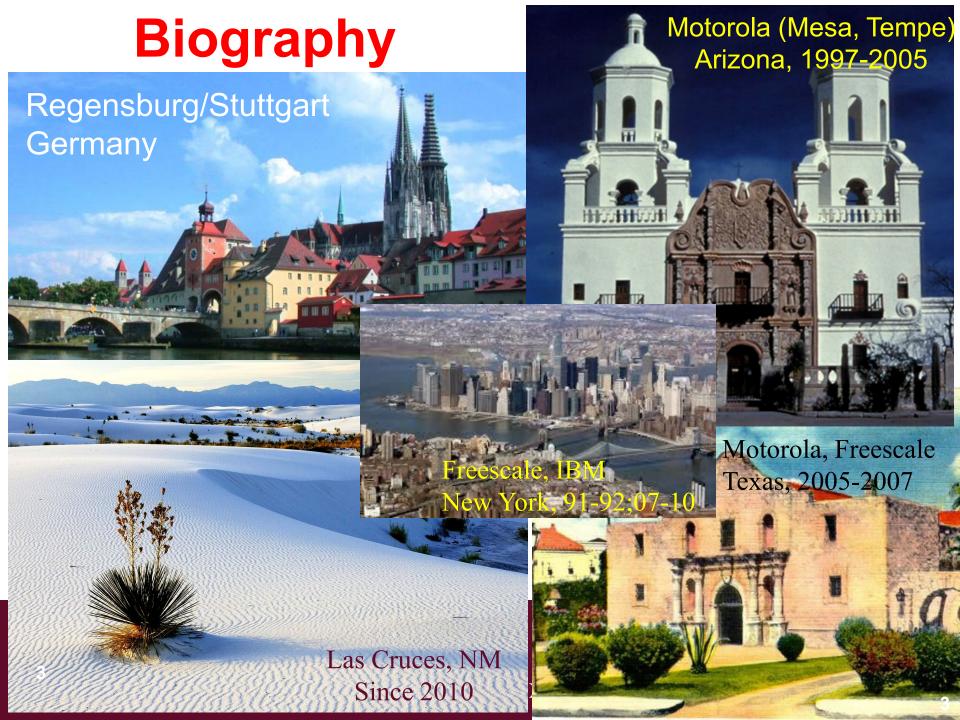
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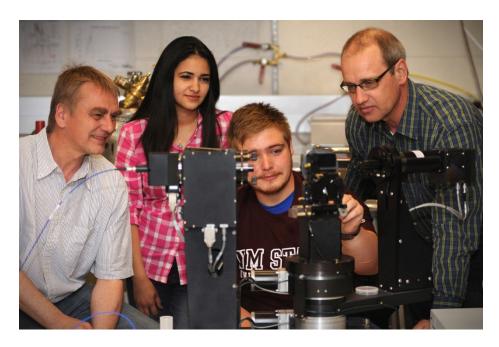
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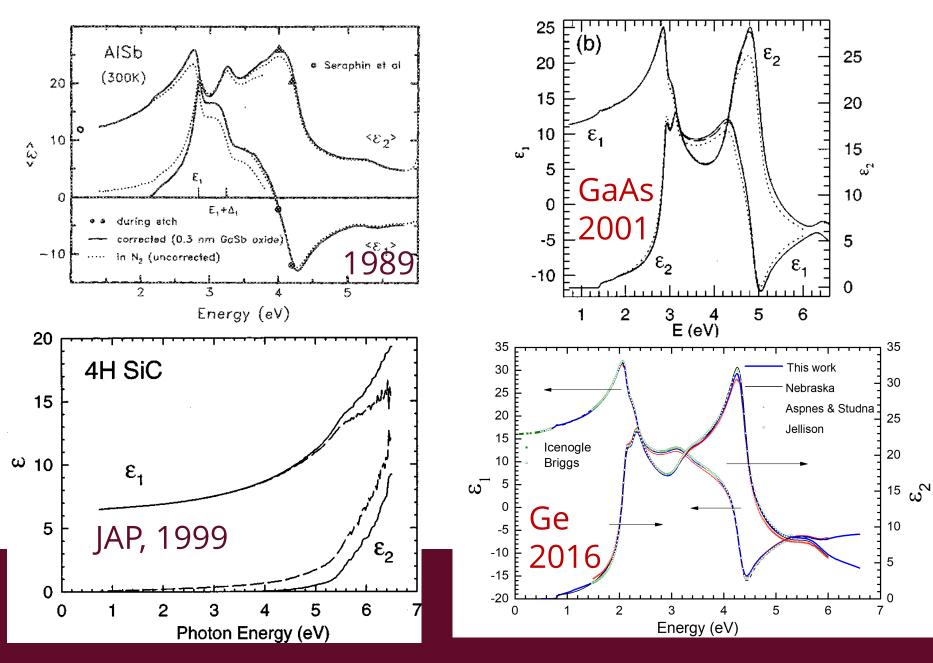
Outline

- Examples of single-crystalline semiconductor dielectric functions
- Temperature
- Strain
- Alloy composition
- Excitonic effects
- Film thickness
- Doping and carriers

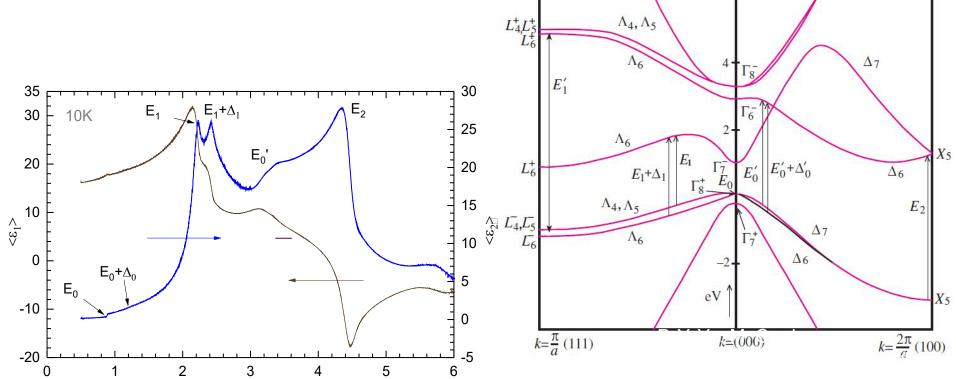




Semiconductor Dielectric Functions



Critical points in the dielectric function are related to interband transitions

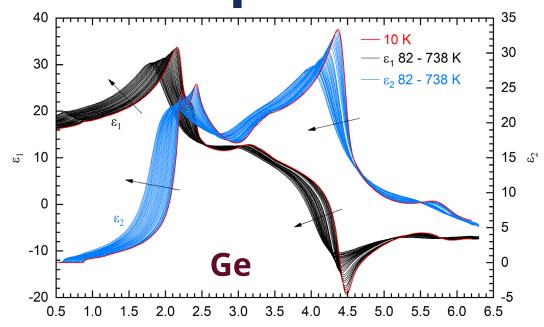


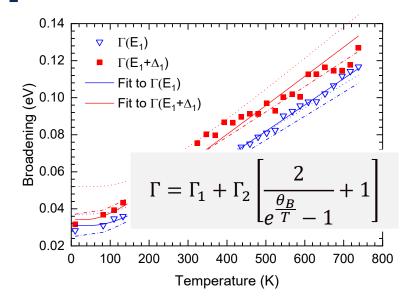


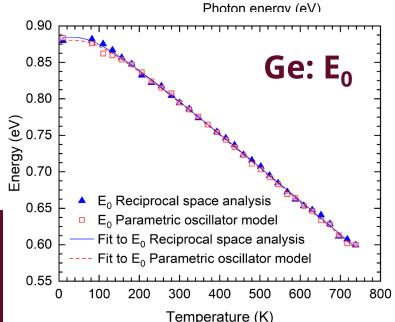


Photon energy (eV)

Impact of Temperature





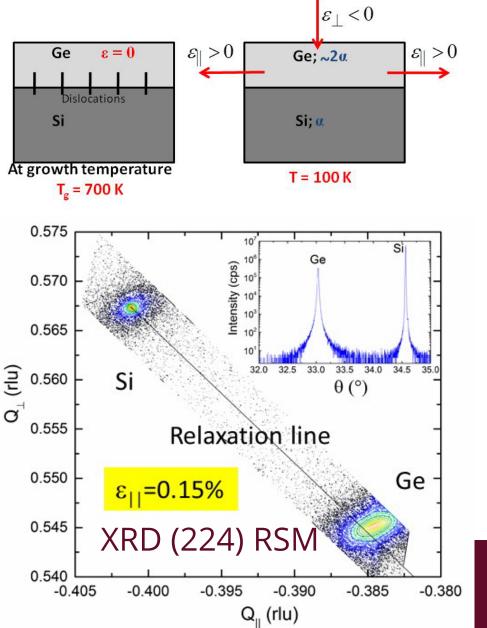


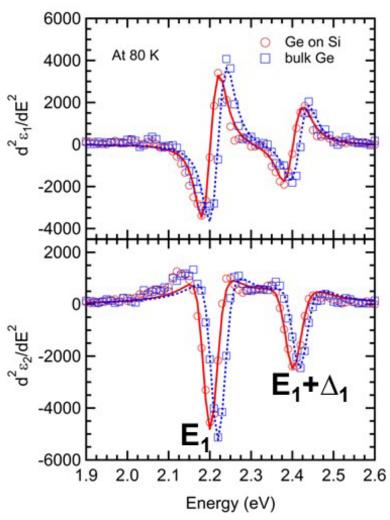
Thermal expansion (small)
Electron-phonon interaction
(dynamic disorder)

Red-shift and broadening of CPs
Theory exists (e-phonon coupling)

Carola Emminger, MS thesis (Linz)

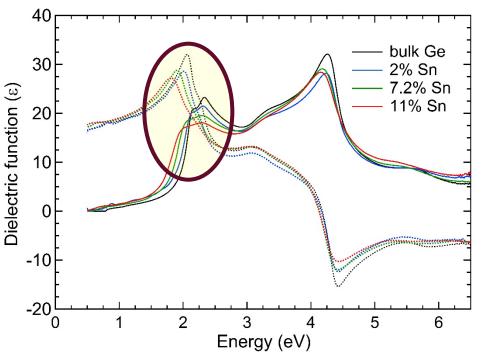
Impact of Strain and Stress

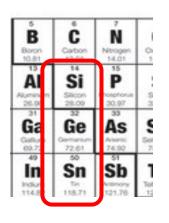




Continuum elasticity theory
Deformation potentials

Impact of Composition: Ge-Sn Alloys





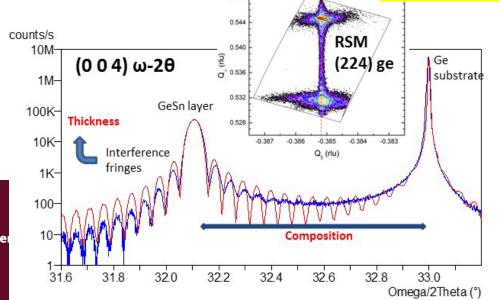


Fully strained

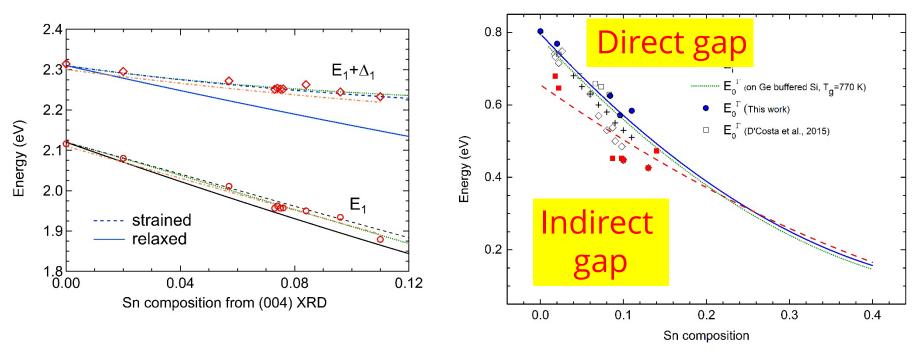
N. Fernando, JVST B 36 (2018)

Impact of Sn:

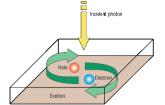
- Redshift
- Broadening
- Increase of Δ_1
- Same theory as temperature effects



Impact of Composition: Ge-Sn Alloys



Significant difference between <u>pseudomorphic</u> Ge-Sn alloys (grown on Ge) and <u>relaxed alloys</u> (grown on Si). Only relaxed Ge-Sn alloys become direct semiconductors (10% Sn).

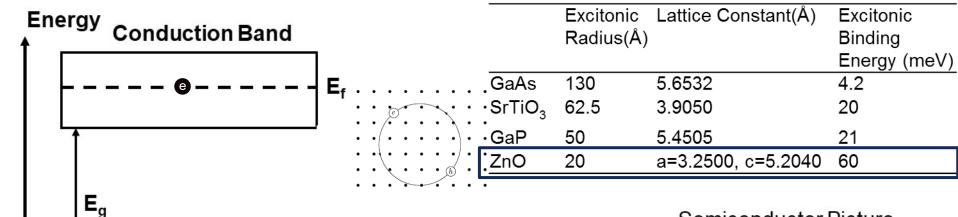


The Concept of an Exciton

Exciton: bound electron – hole pair

Wannier exciton

(typical of inorganic semiconductors)



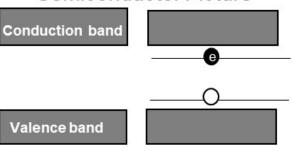
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Valence Band

Large radius (larger than atomic spacing)

Weakly bound

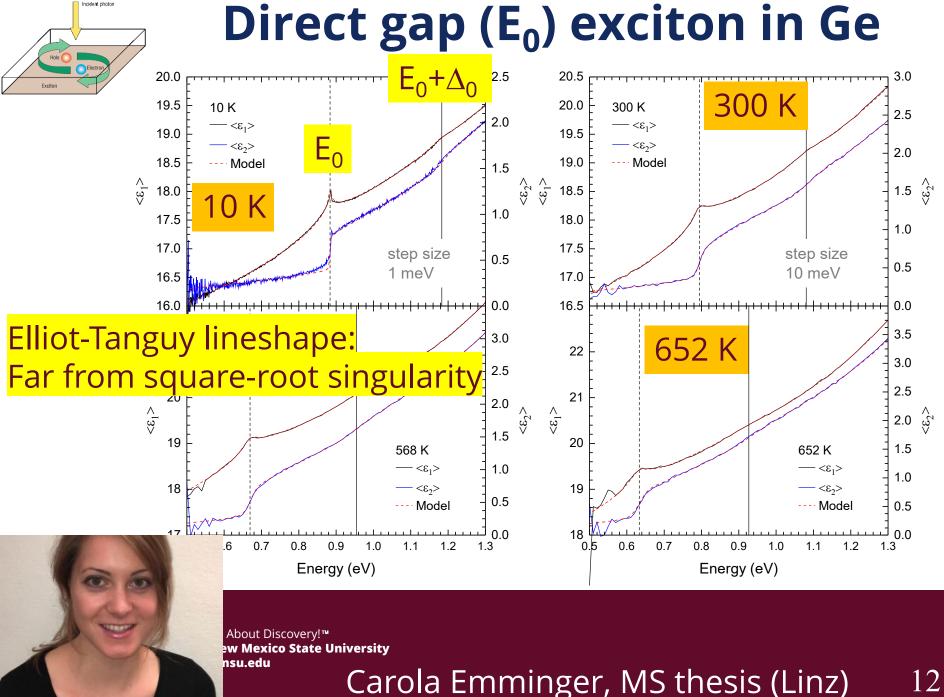
Semiconductor Picture



Electron+Hole Wannier Exciton

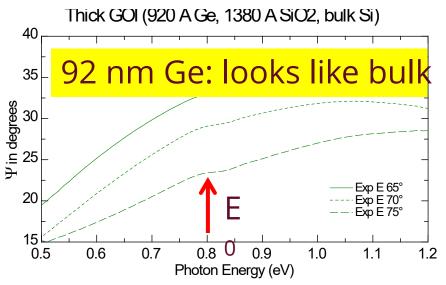


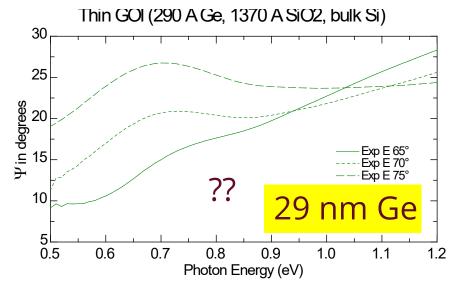
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Incident photon

Impact of Film Thickness: Ge on SiO₂





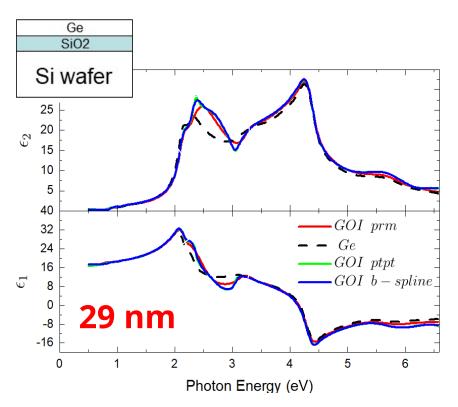
Ge Si02 Si wafer

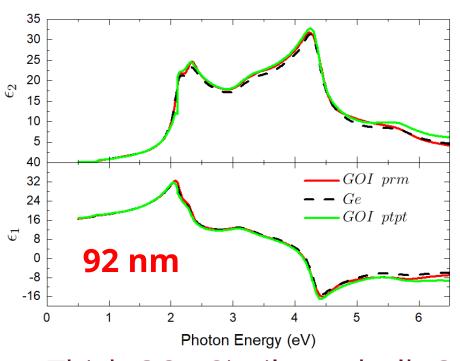
GOI: Ge on insulator, produced by SmartCut process

Possible confinement shift of E_0 by 10-30 meV (very hard to see at 300 K, need low temperature data)



Impact of Film Thickness: Ge on SiO₂





Thin GOI: Blueshift of E_1 and $E_1+\Delta_1$ (about 100 meV)

Thick GOI: Similar to bulk Ge

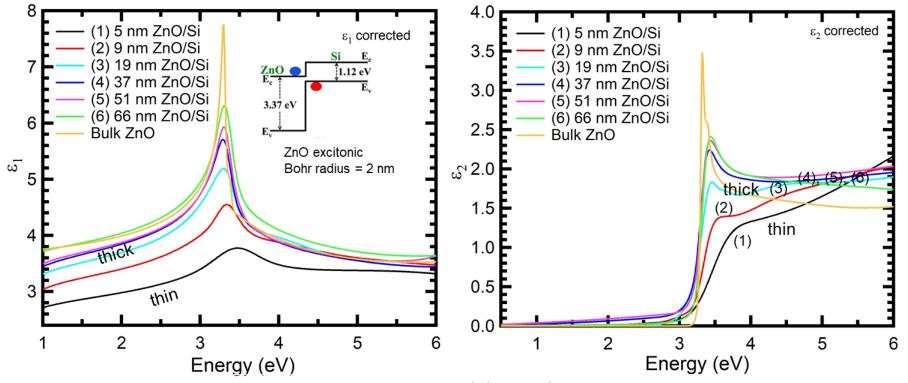


Observed blueshift (100 meV) in thin GOI hard to explain with strain of confinement

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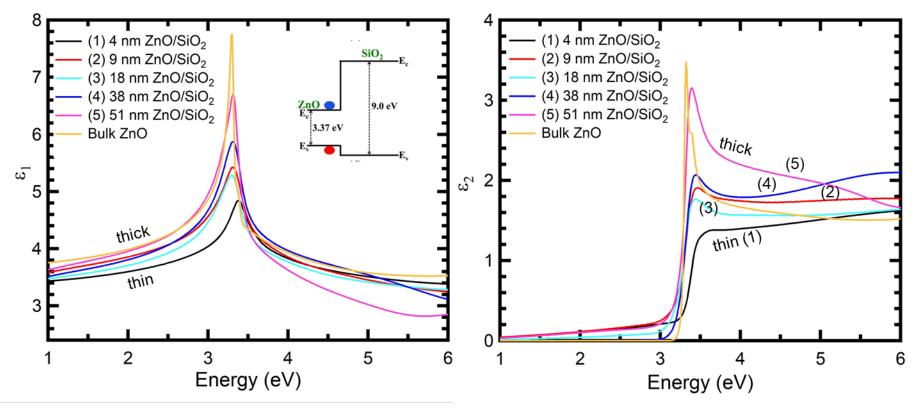
Impact of Film Thickness: ZnO on Si



Kramers–Kronig consistent modeling with Tauc-Lorentz oscillators.

 Real and imaginary parts of dielectric function of ZnO layers on Si decrease monotonically with decreasing thickness.

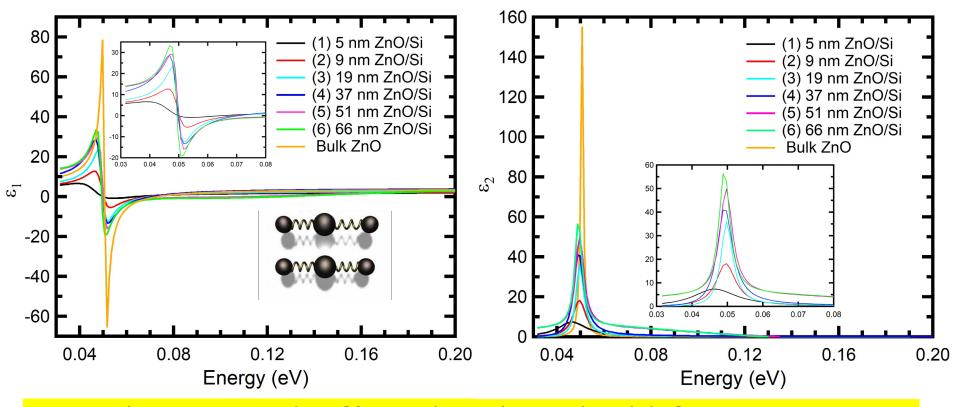
Impact of Thickness: ZnO on SiO₂



- Real and imaginary parts of dielectric function of ZnO layers on SiO₂ also decrease monotonically with decreasing thickness.
- Explanation: Exciton dephasing at type-II quantum well interface.



Lattice vibrations in thin ZnO on Si



- TO absorption in thin films is broader and redshifts.
- Explanation: Damping of oscillations, if thickness below mean free

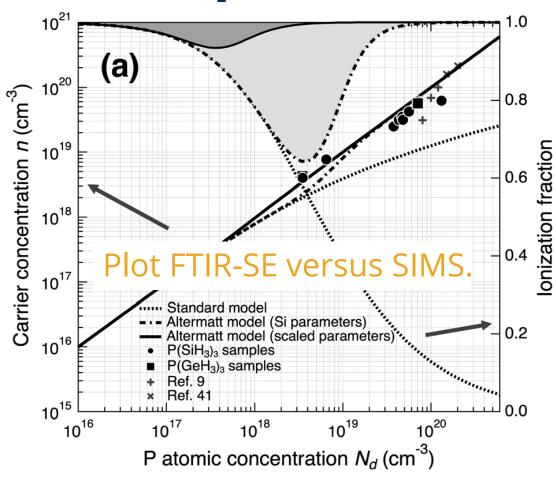


Impact of Doping

- Doping: Impurities plus free carriers
- <u>Dopant activation:</u> How many impurities are ionized, produce free carriers?
- Impurities:
 - Impurity (alloy) scattering due to lattice potential disorder
 - Compensation doping (electrons plus holes)
 - Strain effects if atomic radii of impurity and host differ
- Free carrier effects:
 - Drude response
 - Band gap renormalization (BGR)
 - Band gap filling or Pauli blocking
 - Burstein-Moss shift
 - Reduction of excitonic effects
- <u>Photoexcitation:</u> Equal number of electrons and holes add to existing carriers (from doping)



Dopant Activation (Ge:P)



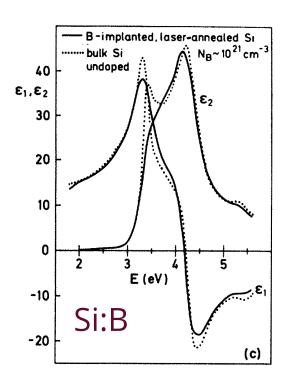
Nearly complete donor ionization is possible in Ge:P, as long as all donors are in substitutional lattice sites (avoid donor clusters and interstitial donor atoms).

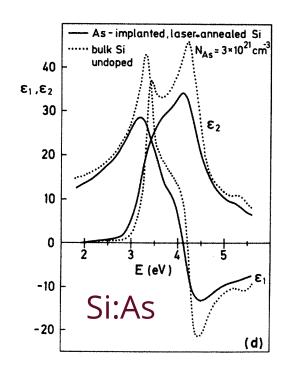
Ionization fraction only depends on quality of samples.

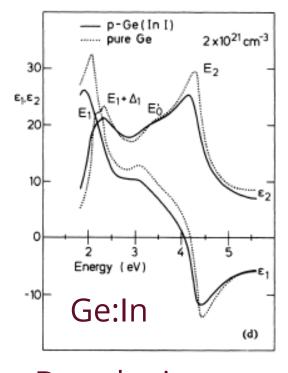
In situ doping methods preferred.



Highly doped Si and Ge







E₁ Exciton weakened

E₁ Exciton weakened Broadening

Broadening
No amplitude reduction



E₁ excitonic enhancement strong in Si, weak in Ge.

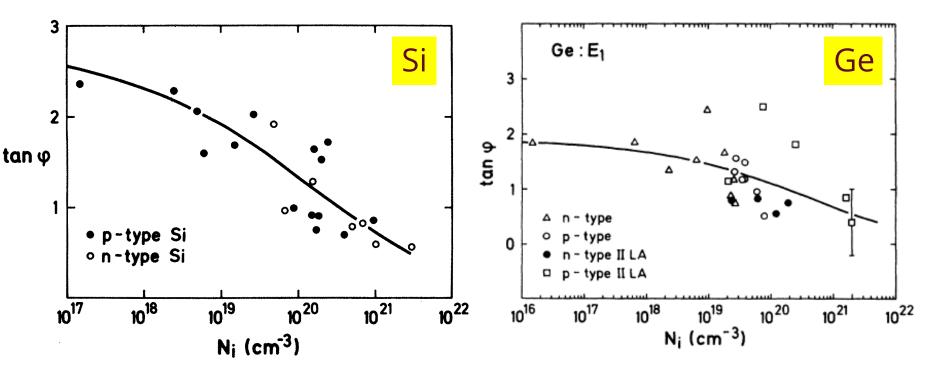
Excitonic Effects (doping)

- In some semiconductors, strong excitonic contributions to the E_1 and $E_1+\Delta_1$ critical points.
- Si and GaAs: Strong E₁ excitons; Ge: Weak E₁ excitons.
- Si: Strong dephasing at 6E20 P doping, when the Thomas-Fermi screening length (0.5 nm) is smaller than the excitonic radius (3 nm).
- Si: Strong reduction of E₁ amplitude, but no shift.
- Ge: Not much amplitude reduction (band filling), but redshift and broadening due to impurities.
- Excitonic screening changes the E₁ phase angle (Si, Ge, alloys) due to impurities and alloy disorder.
- Compare Raman scattering in doped Ge at E₁ resonance.



Excitonic Effects: E₁ phase angle

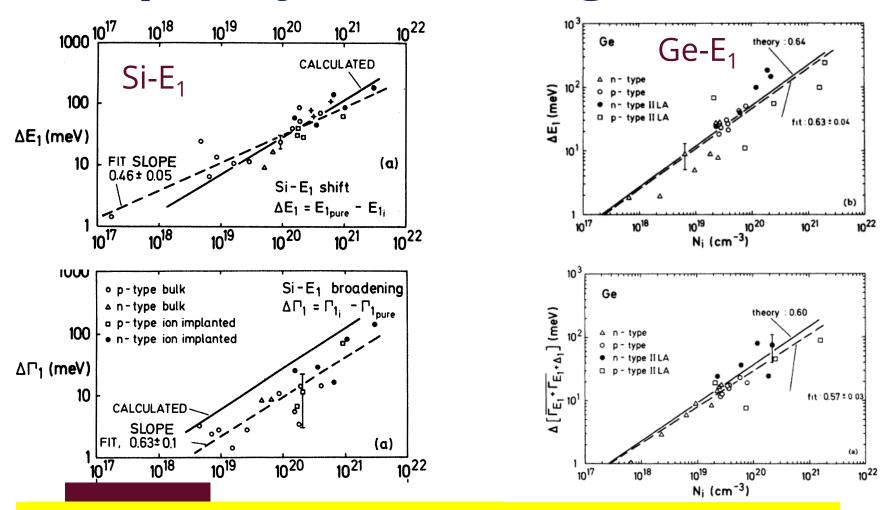
Excitonic screening changes the E₁ phase angle
 (Si, Ge, alloys) due to impurities and alloy disorder.





Similar reduction in E₁ phase angle for Si and Ge.

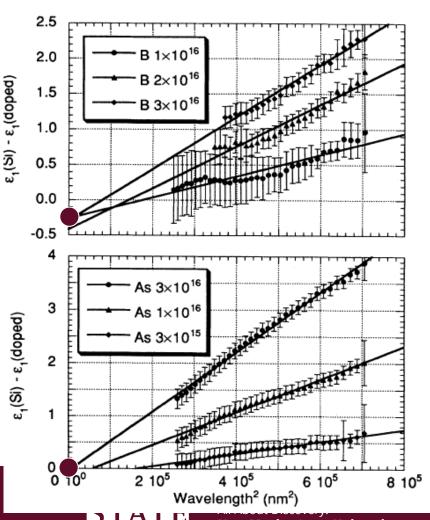
Impurity Scattering: Si and Ge

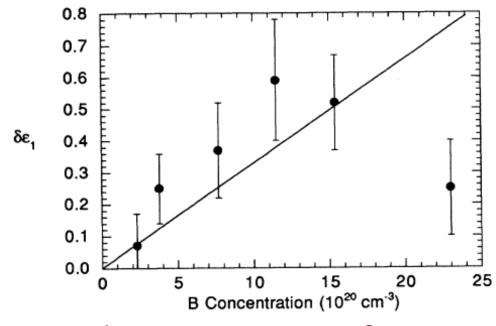


Static Disorder (alloy scattering): Similar redshift and broadening as with temperature.

Strain Effects in doped Si

Measurable if atomic radii of impurity and host differ





Boron doping 2.3E21 cm⁻³ Out-of-plain strain $\varepsilon_{\mathbb{P}}$ =1.1% ε_{1} changes (piezo-optic coefficients)

Strain Effects in doped Ge

Covalent atomic radii (Phillips)

В	С	N
0.853	0.744	0.719
Al	Si	P
1.230	1.173	1.128
Ga 1.225	Ge	As
	1.225	1.225
In	Sn	Sb
1.405	1.405	1.405

$$\beta_{P}^{Ge} = \left(\frac{2}{4.418 \times 10^{22} \text{ cm}^{-3}}\right) \left(\frac{1.128 - 1.225}{1.225}\right) =$$

$$= 4.527 \times 10^{-23} \text{ cm}^{3} \times \left(-0.0791\right) = -3.58 \times 10^{-24} \text{ cm}^{3}$$

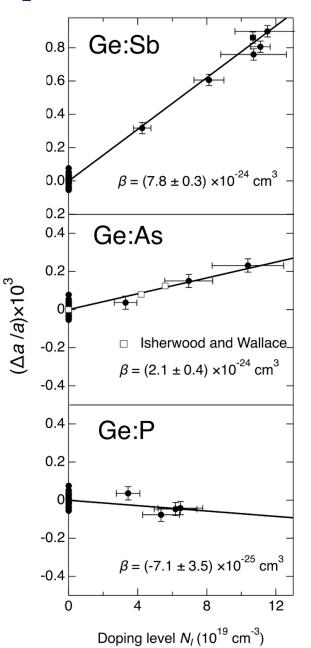
$$\beta_{\text{As}}^{\text{Ge}} = 4.527 \times 10^{-23} \text{ cm}^3 \times \left(\frac{1.225 - 1.225}{1.225} \right) = 0 \text{ cm}^3$$

$$eta_{ ext{Sb}}^{ ext{Ge}} = 4.527 imes 10^{-23} \ ext{cm}^3 imes \left(rac{1.405 - 1.225}{1.225}
ight) = 6.65 imes 10^{-24} \ ext{cm}^3$$



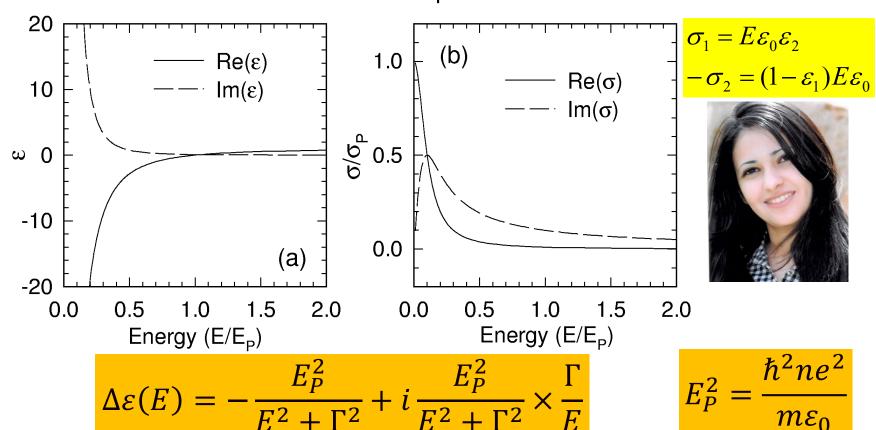
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J. Menendez (ASU)



Drude Model for Metals

Drude model, $\Gamma/E_p=0.1$

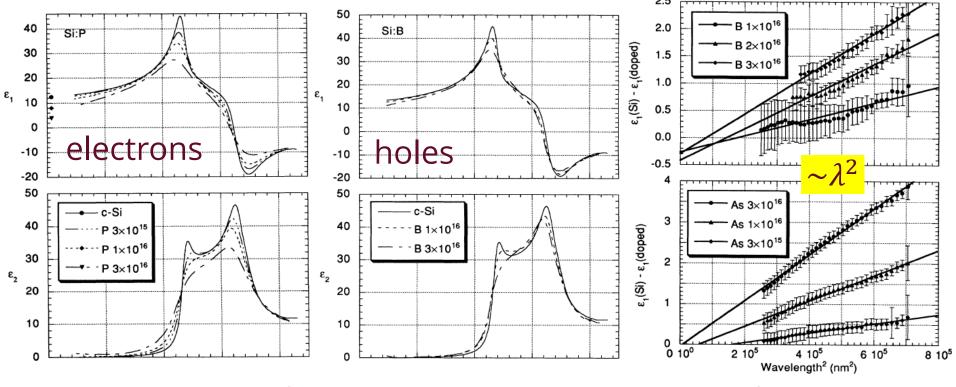




 $\Delta \epsilon$ proportional to λ^2 for small Γ (slope n/m). Only $\Delta \epsilon_1$ measurable for small Γ .

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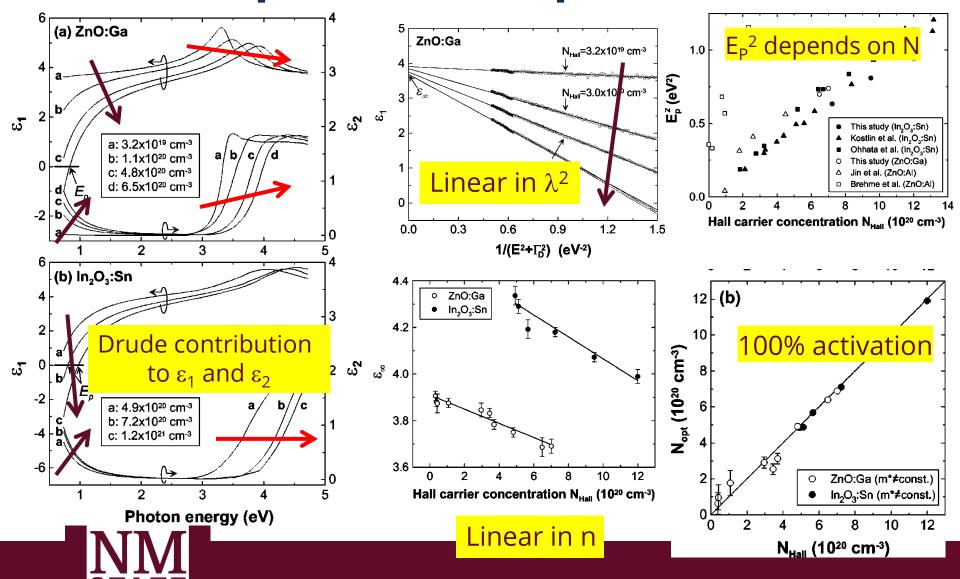
Drude Response for doped Si



Clear reduction of ε_1 below the direct gap due to free carriers. Change in ε_2 is due to impurity scattering, not free carriers. Electrons contribute more than holes (smaller mass). Doping with P and As has similar results (not shown).

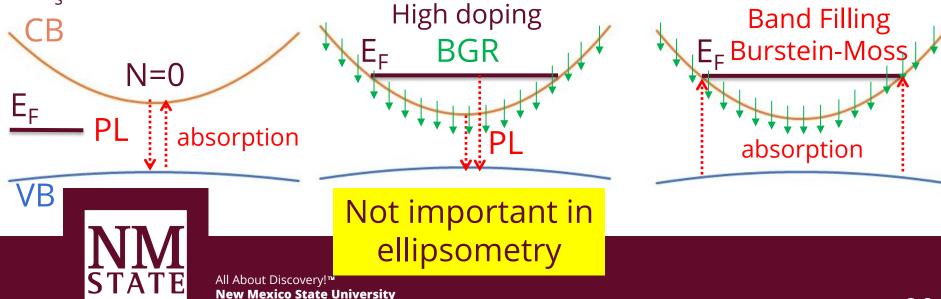


Drude Response for doped ZnO and ITO



Many-Body Effects

- Band gap renormalization (BGR)
 - Band gap is lowered at high carrier density
 - Measurable with photoluminescence
- Band filling or Pauli blocking
 - Band filling affects absorption measurements
- Burstein-Moss shift
 - Absorption threshold affected by both BGR and band filling
- Mott transition: Individual excitons versus electron-hole liquid (EHL) at r_s~5.

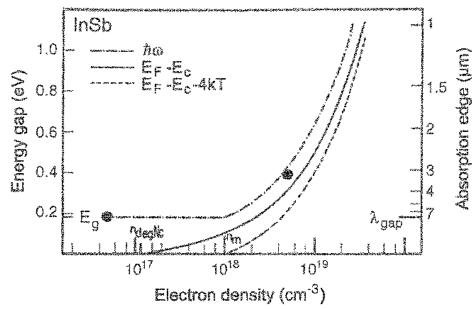


Band gap filling

- Filled electron and hole states reduce absorption probability by a factor 1-f_e-f_h, where f is the population of the state.
- Also known as Pauli blocking.
- Bleaches the absorption, spectral hole burning.
- Purely quantum mechanical effect (Fermi statistics).

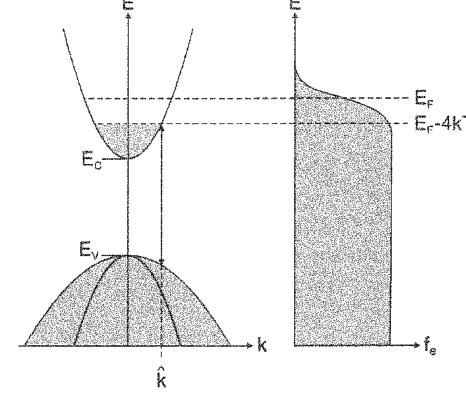


Burstein-Moss Shift: n-type InSb



Absorption threshold increases, because CB bottom is filled with electrons (Pauli

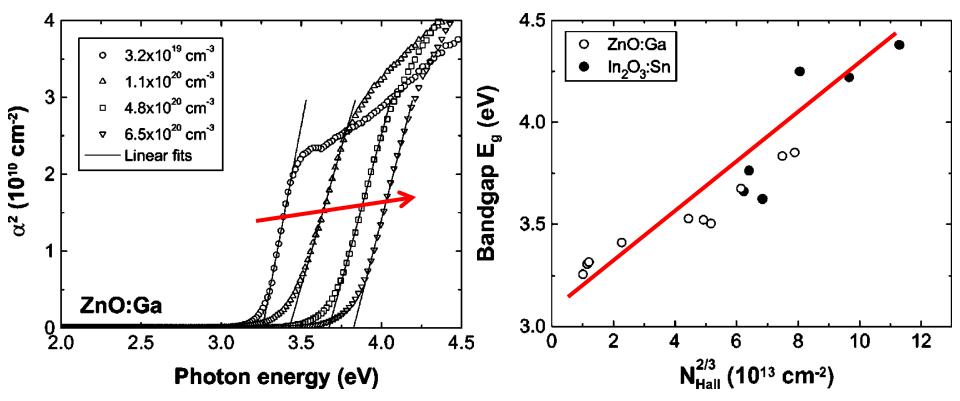






$$\Delta E = (E_F - 4kT - E_{CB}) \left(1 + \frac{m_e}{m_h} \right) \approx \frac{h^2}{8m_r} n^{2/3}$$

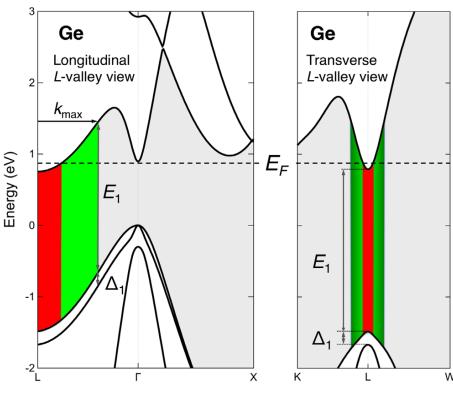
Burstein-Moss Shift in ZnO and ITO



Band gap **increases** with increasing dopant concentration. Band gap renormalization (decrease) PLUS band filling (increase Shift is proportional to $n^{2/3}$ (many-body effect).



E₁ gap in highly doped Ge:P



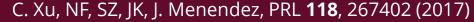
$$\varepsilon_2(E) = \frac{8e^2\bar{P}^2\mu_\perp}{3m^2E^2}H(E - E_1) \times$$

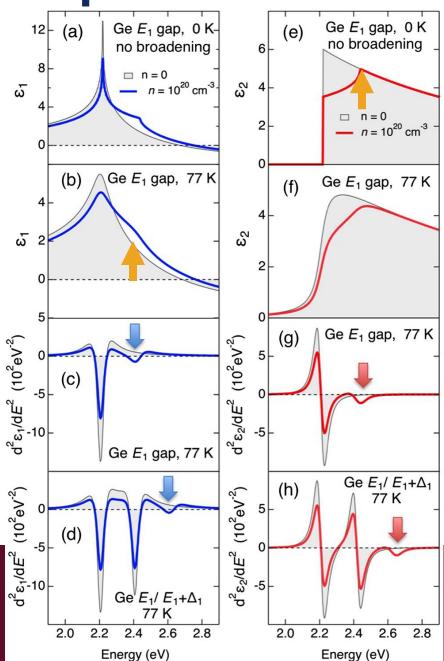
$$\times \int_{-k_{max}}^{k_{max}} dk_z \{1 - f[E_c(E, k_z^2)]\}$$

STA Phase-filling singularity

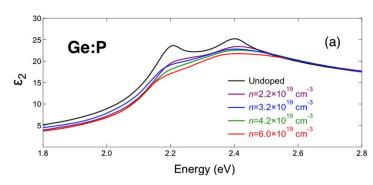
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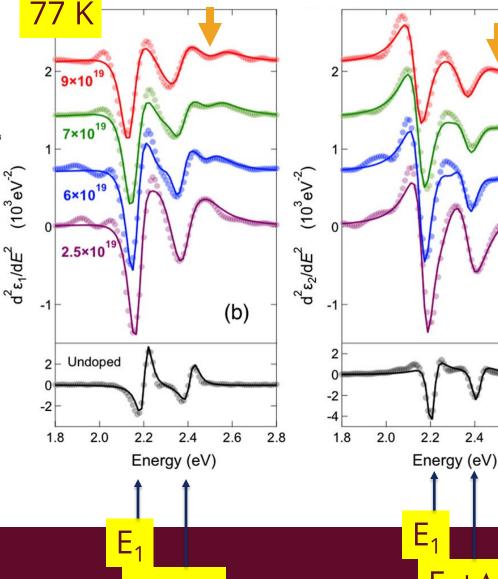


Phase-filling singularity in highly doped Ge:P



$$\begin{split} \varepsilon_2(E) &= \frac{8e^2\bar{P}^2\mu_\perp}{3m^2E^2}H(E-E_1) \mathbf{\times} \\ &\qquad \mathbf{\times} \int\limits_{-k_{\max}}^{k_{\max}} dk_z \{1-f[E_c(E,k_z^2)]\} \end{split}$$

Phase-filling singularity



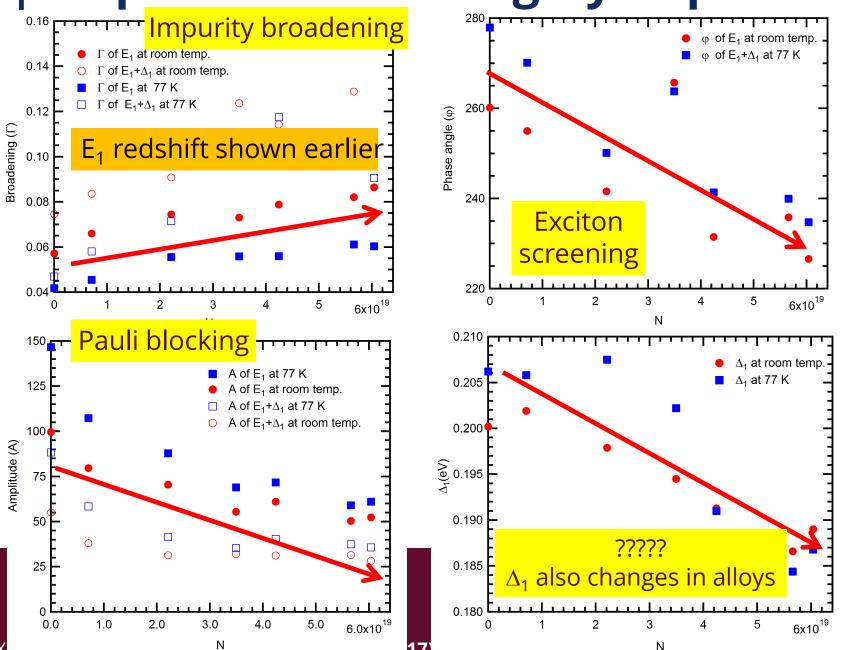
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 $E_1 + \Delta_1$

C. Xu, NF, SZ, JK, J. Menendez, PRL **118**, 267402 <u>(2017)</u>

(c)

E₁ CP parameters in highly doped Ge:P



Summary

Dielectric functions of semiconductors depend on

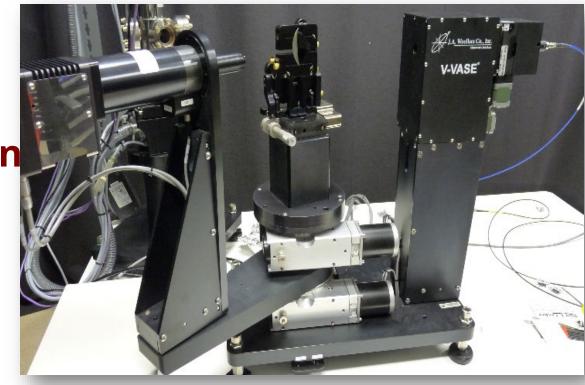
many parameters:

Temperature

Strain

Alloy composition

- Doping
- Free carriers
- Excitonic effects
- Film thickness







Backup



Band-gap renormalization (BGR)

- Modified Rydberg units make BGR independent of material:
 - Excitonic Rydberg R (exciton binding energy: mass m* + screening ε)
 - Excitonic Bohr radius a_B
 - Carrier separation r_s : $n^{-1}=(4\pi/3)(r_s a_B)^3$
 - Reduced density: $\mathcal{N}=na_{B}^{3}$; reduced temperature: $\mathcal{G}=kT/R$.

Exchange energy:

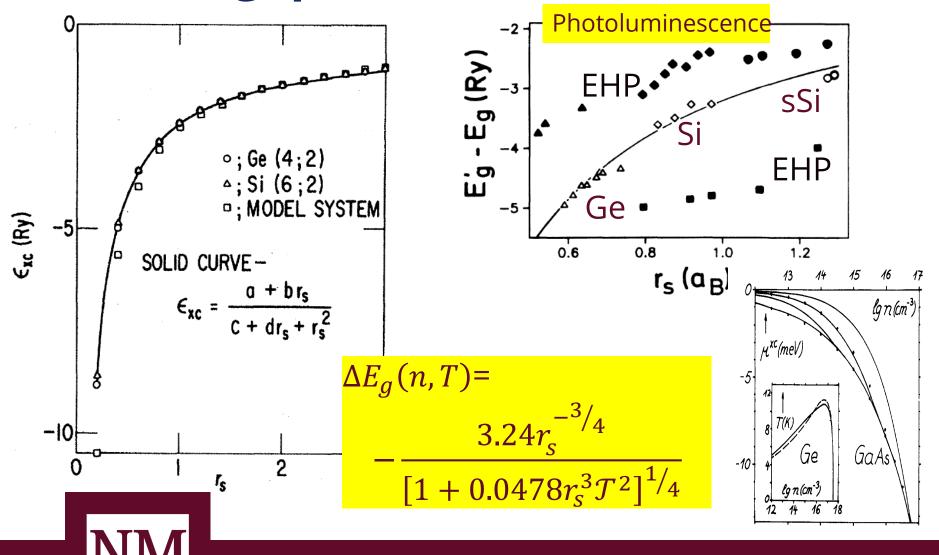
- ΔE_g (exchange)= $-1.22/r_s$ (single isotropic valley), proportional to $n^{1/3}$.
- Modify expression for multiple or anisotropic valleys
- Ge at n=4.3E19cm⁻³: ΔE_g (exchange)=-0.02 eV (observed: -0.07 eV)
- Electrons in L-valley of Ge do not impact direct band gap BGR, because wave functions at L and Γ do not overlap. Exchange energy between electrons in different valleys vanishes. Compare Kalt&Rinker, PRB **45**, 1139 (1992).

Summary:

- Band gap renormalization in doped semiconductors is not important, because it is smaller than the impurity shifts observed by Vina.
- BGR is the dominant influence in photoexcited semiconductors (PL experiments).



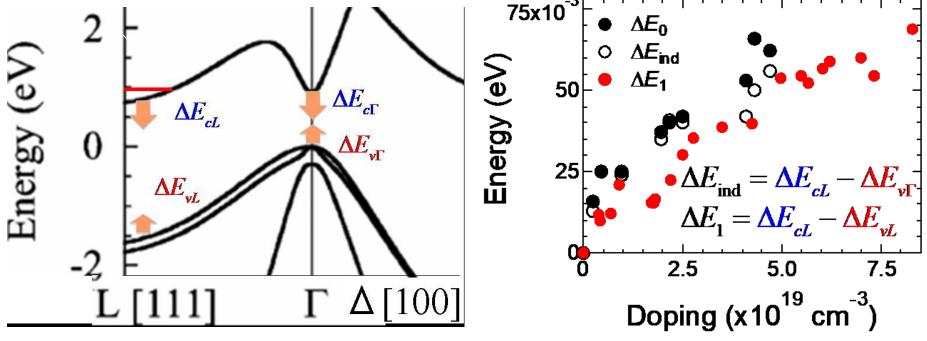
Band-gap renormalization (BGR)



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P. Vashista and R.K. Kalia, Phys. Rev. B **25**, 6492 (1982). A. Forchel, H. Schweizer, and G. Mahler, PRL 51, 501 (1983). New Mexico State University R. Zimmermann, phys. stat. solidi (b) **146**, 371 (1988). S.C. Jain and D.J. Roulston, Solid-State Electron. 34, 453 (1991).

Band gap lowering in Ge:P

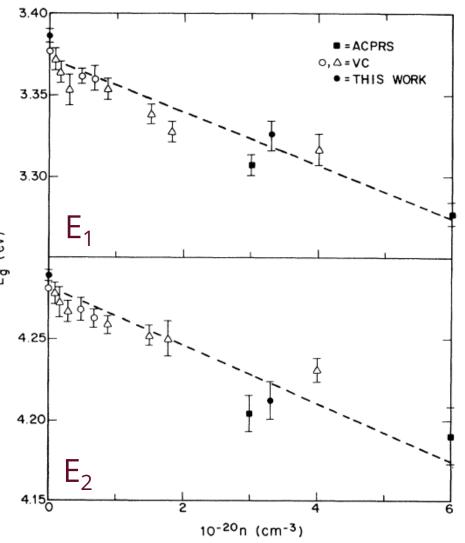


Band gap collapses in Ge:P and Ge:As. (Band filling subtracted.) E_{ind} , E_0 and E_0 collapse at about the same rate, nearly linear in doping density, independent of temperature. Depends on impurity density, independent of n.

s th<mark>is collapse</mark> due to free carriers or <u>due to impurity scattering</u>



Band gap collapse in Si



Is this collapse due to free carriers or due impurity scattering (Viña-like)?

Linear dependence of redshift with dopant density suggests impurity scattering.

 E_1 and E_2 show the same trend. Band gap renormalization should depend on the valley contributing to the CP.

